

## Chemical Preparation and Characterization of Transparent Ferromagnetic Fe:ZnO Semiconductor Films

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Magnetic semiconductors have been attracted much attention as a key material for spin dependent devices (spintronics devices) using optical-magnetic-electrical correlation effects.<sup>1-3</sup> Moreover, ferromagnets with a high optical transparency in visible light region are a novel material and are expected as a device with enhanced magneto-optical effects.<sup>4</sup> Ferromagnetism with Curie temperature enough higher than room temperature and low fabrication costs are required to employ these materials to commonly used devices. Although physical deposition techniques such as a molecular beam epitaxy (MBE) are generally used to prepare magnetic semiconductors, there are some issues on aspects of its mass productivity and costs. In the present study, we investigated a chemical solution process to prepare a transparent ferromagnetic Fe-doped ZnO semiconductor film and its structural, optical, electrical, and magnetic properties.

The Fe-doped ZnO films ( $\text{Fe}_x\text{Zn}_{1-x}\text{O}$ ,  $x \approx 0.19$ ) with 250 nm in thickness were prepared by a simple 2-step procedure composed of (i) chemical deposition of <0001> oriented ZnO film on a catalyzed glass from an aqueous solution<sup>5,6</sup> and (ii) chemical introduction of Fe ions in another aqueous solution to the ZnO film.<sup>7</sup> These solutions contain only the corresponding nitrate salt and dimethyl amineborane (DMAB) and were operated at temperatures of 50-60 °C.

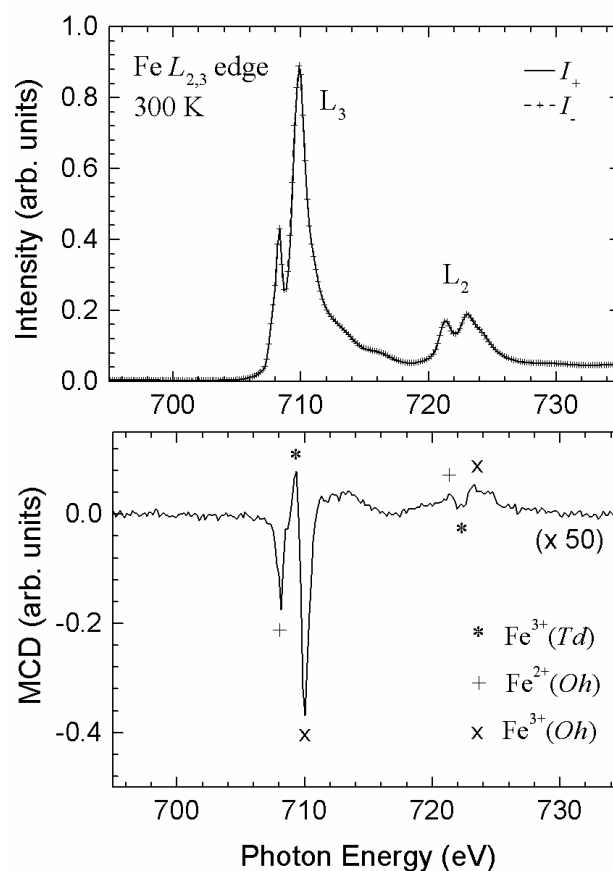
The as-deposited films were analyzed by the following measurements: XRD, UV-VIS photometry, Hall-effects, and VSM. The film showed room temperature ferromagnetism with 7.0 emu  $\text{cm}^{-3}$  in saturation magnetization and 60 Oe in coercive force and high transparency in visible light regions as well as *n*-type semiconducting feature with 3.6  $\text{cm}^2 \text{V}^{-1} \text{s}^{-1}$  in mobility and  $1.0 \times 10^{10} \text{ cm}^{-3}$  in carrier concentration. In the XRD pattern for the film, no reflections assigned as iron compounds could be observed and the film was identified as <0001> oriented ZnO with wurtzite structure. Differences in peak position and FWHM of 0002 reflection could not be recognized among the ZnO and Fe:ZnO films.

In order to clarify the origin of room temperature ferromagnetism of the Fe:ZnO film, we measured x-ray absorption fine structure (XAFS) and soft x-ray magnetic circular dichroism (SXMCD) at Fe and Zn *K*, *L*<sub>2,3</sub> edges in Japan Synchrotron Radiation Institute (JASRI), SPring-8. X-ray absorption near-edge structure (XANES) indicated that ferric and ferrous ions are contained in the film, and  $k^3$  weighted EXAFS oscillation  $k^3\chi(k)$ , where *k* is wave number, revealed that the local structure around the introduced iron was analogous to that of bulk

ferromagnetic magnetite ( $\text{Fe}_3\text{O}_4$ ). In an SXMCD measurement on Fe *L*<sub>2,3</sub> edges, MCD was observed as shown in Figure 1. The MCD spectrum for the Fe:ZnO film was almost the same in profile and peak energies as those for ferrites with a spinel structure containing ferric ions on the tetrahedral and octahedral sites and ferrous ions on the octahedral sites. The peak intensity ratio was slightly different to those for stoichiometric  $\text{Fe}_3\text{O}_4$ , suggesting that the Fe:ZnO film contained non-stoichiometric  $\text{Fe}_3\text{O}_4$  to some extent.

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**Figure 1.** Normalized Fe *L*<sub>2,3</sub> XAS (top) and MCD (bottom) spectra for the  $\text{Fe}_{0.19}\text{Zn}_{0.81}\text{O}$  film at 300 K. The curves  $I_+$  ( $I_-$ ) represent the XAS intensity for the right (left) circularly polarized light, respectively.